

S/N Unknown

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: John Whitman

Examiner: Unknown

Serial No.: Unknown

Group Art Unit: Unknown

Filed: Herewith

Docket: 303.254US4

Title: A SOLVENT PREWET AND METHOD TO DISPENSE THE SOLVENT  
PREWET

#3 Pre.A  
PLH  
12-13-01

PRELIMINARY AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

Before taking up the above-identified application for examination, please enter the following amendments.

IN THE DRAWINGS

Enclosed is a copy of Figure 1 of the drawings showing the following proposed amendment to Figure 1 in red ink.

The proposed amendment is to include the legend PRIOR ART to Figure 1 as it illustrates a conventional track coating unit,

IN THE ABSTRACT OF THE DISCLOSURE

Please substitute the Abstract in the appendix entitled Clean Version of Abstract for the previous Abstract. Following is a marked-up version of the Abstract:

A method and apparatus is provided for more [efficiently] efficient application of photoresist to a wafer surface. One aspect of the method comprises applying solvent to the wafer and spinning it to coat the entire wafer surface prior to the application of photoresist. This reduces surface tension on the wafer and reduces the amount of resist required to achieve a high quality film. The apparatus comprises adding a third solenoid and nozzle to the coating unit to accommodate the application of solvent to the center of the wafer surface. The method also describes incorporating a new solvent comprising [Di-Acetone Alcohol] diacetone alcohol, which is a low-pressure solvent, providing extended process latitudes and reduced material expenditures.